The following listing of claims will replace all prior versions, and listings, of

claims in the application:

Listing of Claims:

1. (Previously Presented) A semiconductor device comprising:

a semiconductor element;

a first metal plate bonded to one side of the semiconductor element;

an intermediate layer bonded to one side of the first metal plate remote from

the semiconductor element, the intermediate layer being made of a carbon-copper

composite material;

a second metal plate bonded to one side of the intermediate layer remote

from the first metal plate;

an insulating member bonded to one side of the second metal plate remote

from the intermediate layer; and

a third metal plate bonded to one side of the insulating member remote from

the second metal plate, the third metal plate having a thickness substantially equal

to that of the second metal plate; and,

a heat sink;

wherein the first, second and third metal plates are made of a same material.

2. (Previously Presented) The semiconductor device according to claim 1,

Page 3 of 12

Application No.: 10/559923
Amendment Dated: February 1

Amendment Dated: February 19, 2008 Reply to Office action of: January 11, 2008

wherein the intermediate layer is adapted to moderate thermal stress.

3. (Currently Amended) A semiconductor device comprising:

a semiconductor element;

a heat sink; and

a laminar plate provided between the semiconductor element and the heat

sink, said laminar plate including an intermediate layer for moderating thermal

stress,

wherein the laminar plate comprises a first metal plate, the intermediate layer,

a second metal plate, an insulating member, and a third metal plate, wherein:

said first metal plate being interposed between the semiconductor element

and the intermediate layer, said first metal plate having one side bonded to the

semiconductor element and an opposite side bonded to a first side of the

intermediate layer;

said second metal plate being interposed between the intermediate layer and

the insulating member, whereby one side of said second metal plate is bonded to a

second, opposite side of the intermediate layer and the other side of said second

metal plate is bonded to a first side of the intermediate layer; and

said insulating member is interposed between the second and third metal

plates, whereby said third metal plate is bonded to a second, opposite side of the

insulating member.

4. (Cancelled)

Page 4 of 12

Application No.: 10/559923 Amendment Dated: February 19, 2008 Reply to Office action of: January 11, 2008

5. (Currently Amended) The semiconductor device according to claim 4claim

3, wherein a thickness of the second metal plate is equal to a thickness of the third

metal plate.

6. (Previously Presented) The semiconductor device according to claim 3,

wherein the intermediate layer for moderating thermal stress comprises a carbon-

copper composite material.

7. (New) The semiconductor device according to claim 1, wherein the first

metal plate further includes a nickel plating on a surface of the first metal plate to

which the semiconductor element is mounted.

8. (New) The semiconductor device according to claim 1, wherein a

thickness of the second metal plate and the third metal plate is greater than a

thickness of the first metal plate.

9. (New) The semiconductor device according to claim 1, wherein the

insulating member is formed of a material that is an electrical insulator and a thermal

conductor.

10. (New) The semiconductor device according to claim 9, wherein the

insulating member is formed of SiN.

11. (New) The semiconductor device according to claim 3, wherein a

Page 5 of 12

Application No.: 10/559923 Amendment Dated: February 19, 2008 Reply to Office action of: January 11, 2008

thickness of the second metal plate and the third metal plate is greater than a

thickness of the first metal plate.

12. (New) The semiconductor device according to claim 3, wherein the

insulating member is formed of a material that is an electrical insulator and a thermal

conductor.

13. (New) The semiconductor device according to claim 12, wherein the

insulating member is formed of SiN.

14. (New) The semiconductor device according to claim 3, wherein the first

metal plate further includes a nickel plating on a surface of the first metal plate to

which the semiconductor element is mounted.

15. (New) The semiconductor device according to claim 1, wherein the

semiconductor element has a first side and a second side, the first metal plate has a

first side and a second side, and the intermediate layer has a first side and a second

side,

wherein, the semiconductor element second side is directly bonded to the first

side of the metal plate, and the second side of the metal plate is directly bonded to

the first side of the intermediate layer.

16. (New) The semiconductor device according to claim 3, wherein the

semiconductor element has a first side and a second side, the first metal plate has a

Page 6 of 12

Application No.: 10/559923 Amendment Dated: February 19, 2008

Reply to Office action of: January 11, 2008

first side and a second side, and the intermediate layer has a first side and a second

side,

wherein, the semiconductor element second side is directly bonded to the first

side of the metal plate, and the second side of the metal plate is directly bonded to

the first side of the intermediate layer.